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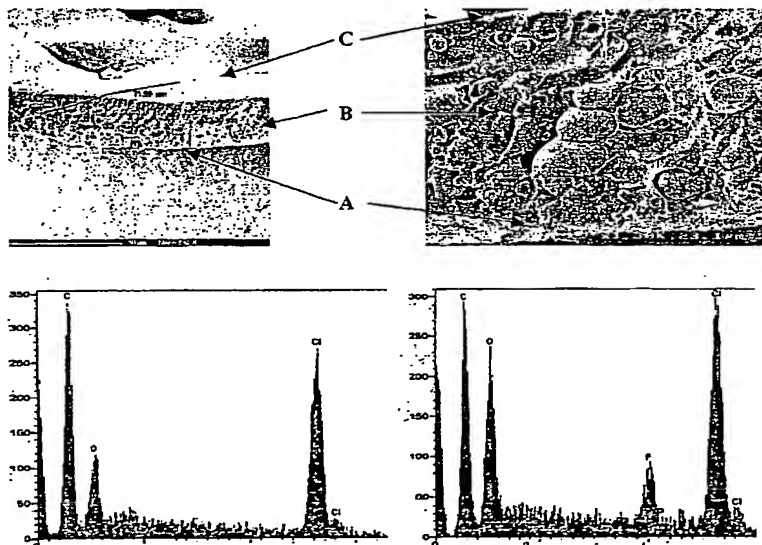
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(54) Title: **POLYMER COMPOSITION**



(57) Abstract: Polymer composition comprising: 1) a polymer (P1) comprising at least 50 % by weight of monomeric units derived from an ethylenically unsaturated monomer (M1), and 2) at least one co-oligomer (O1) comprising at least: a) a component (A) comprising at least one monomeric unit identical to that derived from the monomer (M1) on which the polymer (P1) is based, and b) a component (B) comprising at least one monomeric unit (m2), derived from an ethylenically unsaturated monomer, carrying at least one group chosen from the following groups: $-C_nH_{2n+1}$ with a between 6 and 30; $-(CH_2)_b-C_eF_{2e+1}$ with b between 1 and 11 and c greater than or equal to 5; $-(CH_2)_d-(Si(CH_3)_2-O)_e-Si(CH_3)_3$ with d between 1 and 11 and e between 1 and 1000; $-COOH$; $-SO_3H$, and the phosphonate groups $-PO(OH)(OR_1)$ with R_1 being a hydrogen atom or an alkyl radical containing from 1 to 11 carbon atoms.



PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW.

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